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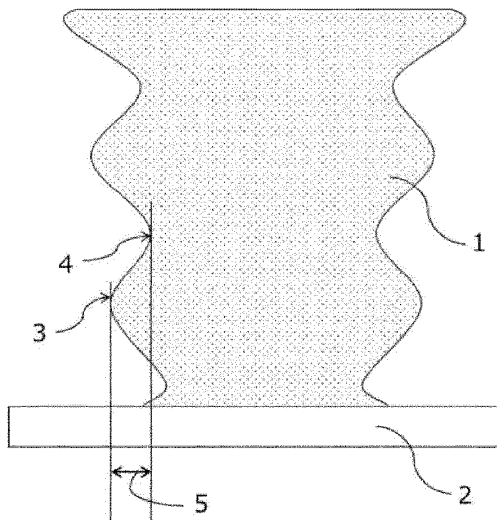


FIG. 1

(57) Abstract: Provided is a substrate coating resist composition containing a polymer (A) having a specific structure and a photoacid generator (B) having a specific structure.

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